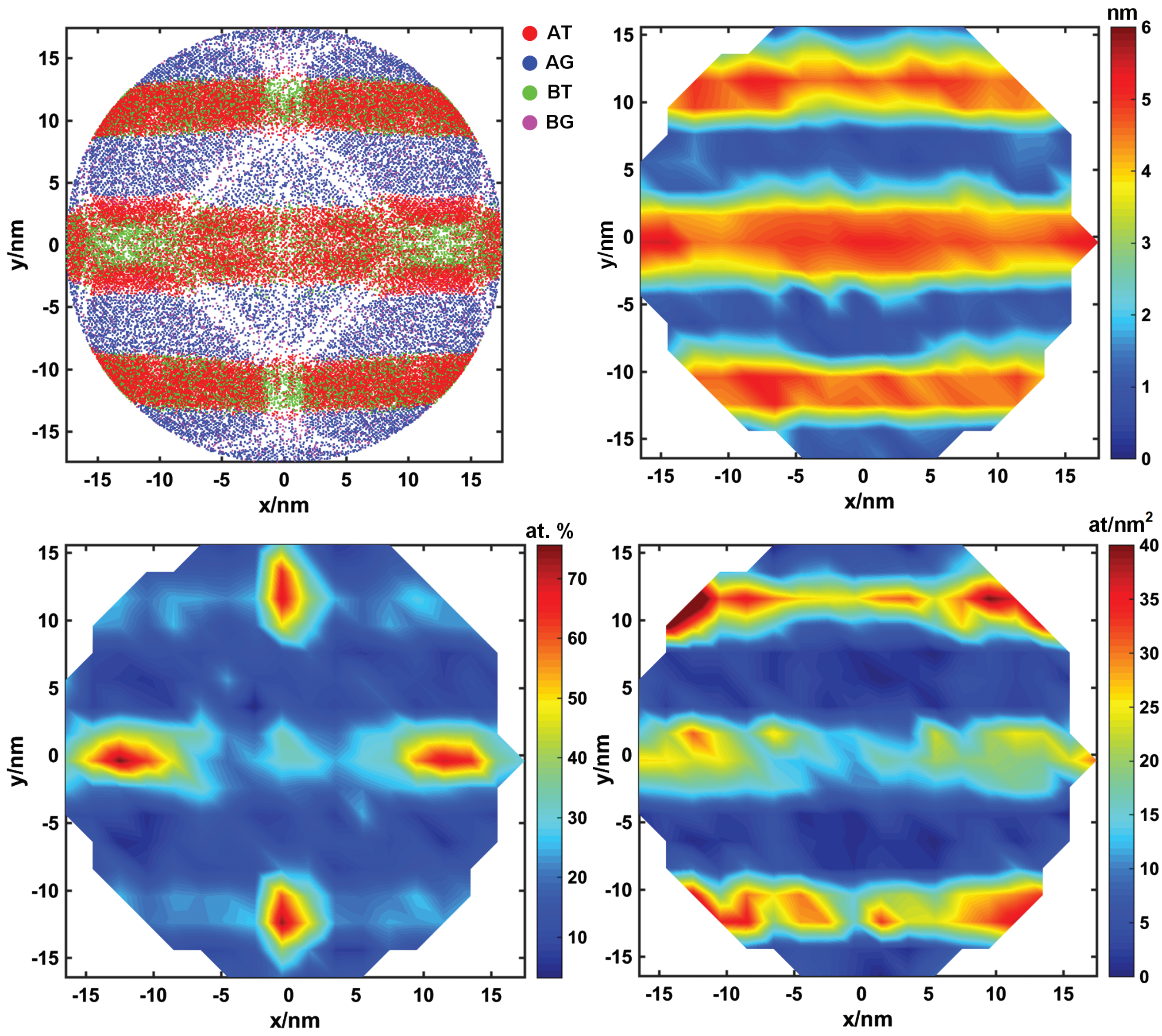
Volume 25, Number 2 April 2019

Microscopy AND Microanalysis



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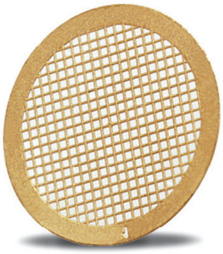
Microscopy Society of America

CAMBRIDGE UNIVERSITY PRESS

ISSN 1431-9276

https://doi.org/10.1017/S1431927619000576 Published online by Cambridge University Press

The C-flat™ Advantage



C-flat™ leads to better data sets.

Made with patented technology, C-flat™ provides an ultra-flat surface that results in better particle dispersion and more uniform ice thickness. Patterning is done using deep-UV projection lithography, ensuring the most accurate and consistent hole shapes and sizes down to submicron features. The precise methods by which C-flat™ is manufactured eliminate artifacts such as excess carbon and edges around holes.

C-flat™ is affordable

C-flat™ is available in 25, 50, and 100 packs at a per-grid price less than competing products.

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- Cryo electron tomography
- Automated TEM analysis

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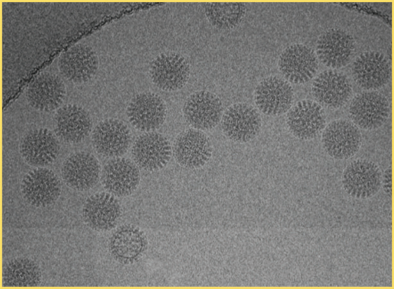
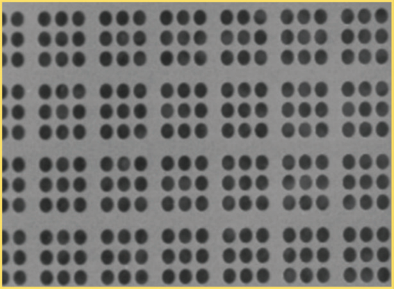


Frozen-hydrated Bacteriophage Capsid (data acquired on CF-1.2/1.4-4C).

Consistent

Researchers around the world have reported that the ultra-flat surface of C-flat™ leads to even ice thickness and uniform particle distribution, allowing for superior 3-D reconstructions. 2 μm hole sizes are standard, but various hole sizes are available to accommodate different particle sizes and magnifications.



Compatible

C-flat™ provides a regular array of analysis sites compatible with automated data collection software such as Leginon. This compatibility, in combination with the more uniform ice thickness and particle distribution reported by numerous researchers, results in more high-quality target sites per grid.

Clean

C-Flat™ uses no plastics or polymers in its production. This means C-Flat™ is shipped clean, so it's ready to use out of the box and requires no solvent washing steps prior to use, leading to less breakage of the holey carbon film.

Expanded Product Line

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An International Journal for the Biological and Physical Sciences

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PUBLISHED IN AFFILIATION WITH

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University of Wisconsin
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David J. Larson
CAMECA
5500 Nobel Drive
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e-mail: david.larson@ametek.com

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Ross Marceau
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P.O. Box 5800, Albuquerque, NM 87185
e-mail: jrmicha@sandia.gov

Yoosuf N. Picard
Materials Science & Engineering
Carnegie Mellon University
Pittsburgh, PA 15213
e-mail: ypicard@cmu.edu

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GE Research
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Dept. of Mater. Sci. & Eng.
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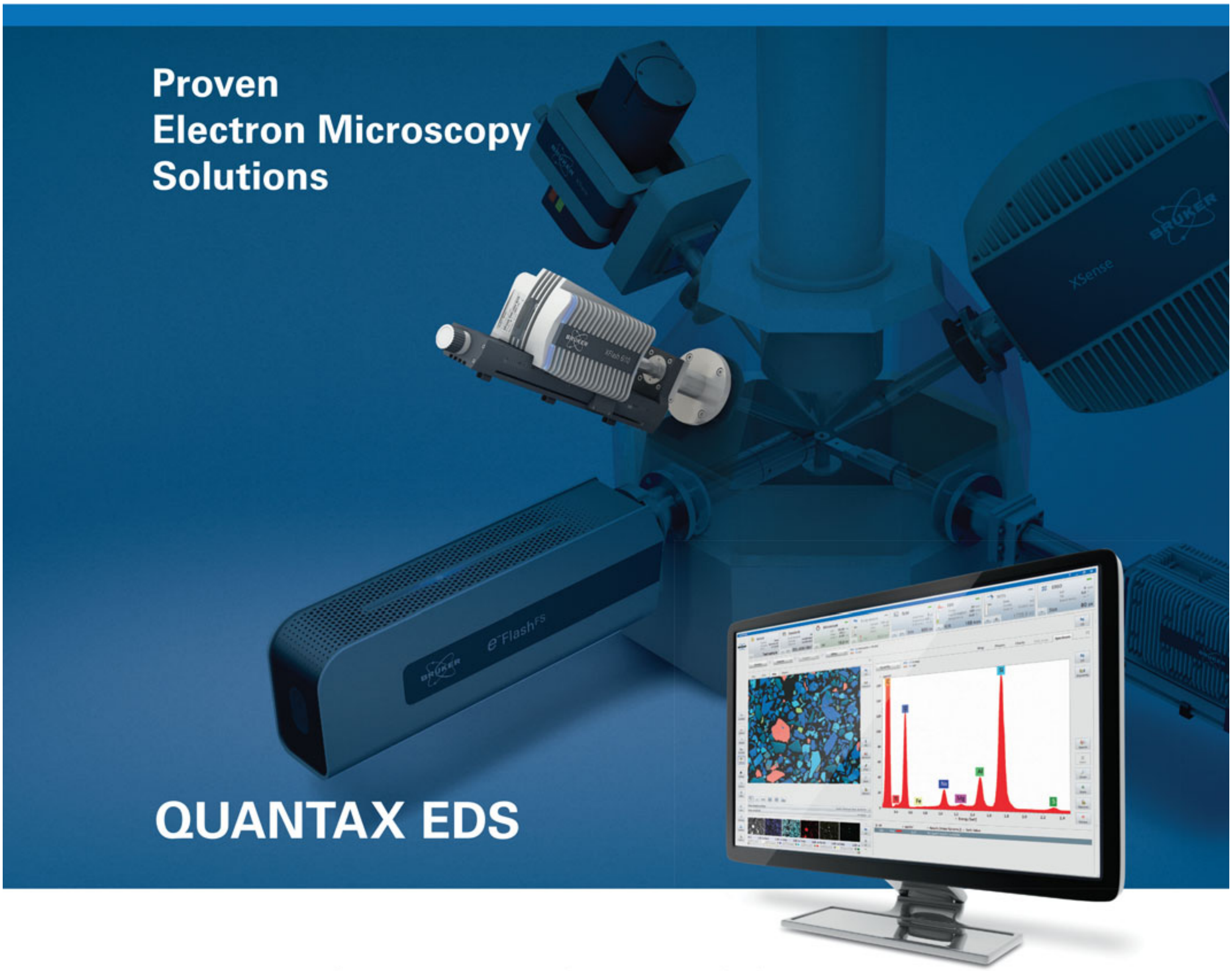

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Microscopy and Microanalysis is published bimonthly in February, April, June, August, October, and December by Cambridge University Press (1 Liberty Plaza, New York, NY 10006). Three supplements (*Meeting Guide, Program Guide, and Proceedings*) are published in June and August.

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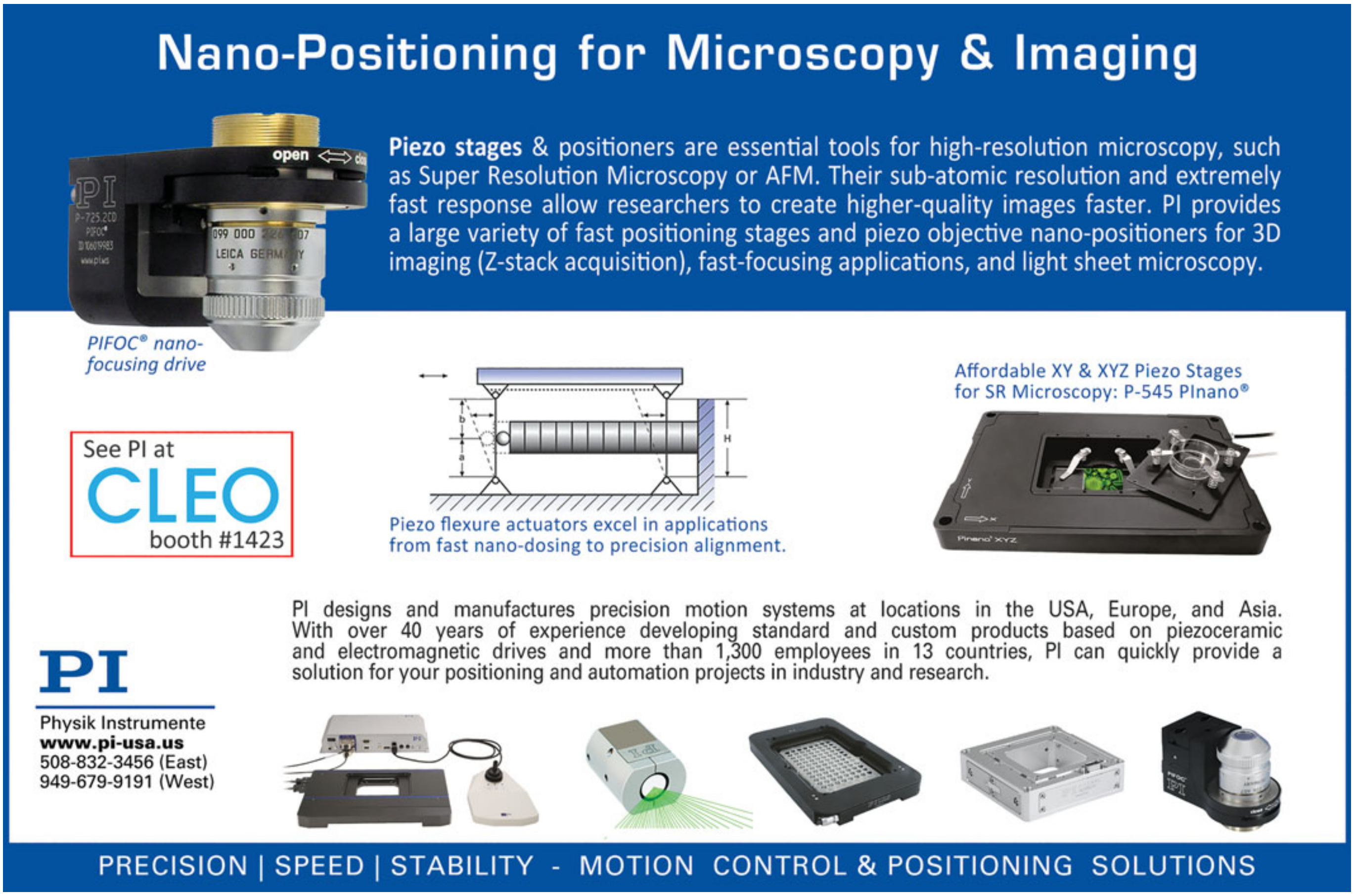

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April 2019

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Atom Probe Tomography and Microscopy
APT&M 2018
Organized under the auspices of the International Field Emission Society
June 10th–15th, 2018, Gaithersburg, Maryland, United States 269

THE ERWIN W. MÜLLER MEMORIAL LECTURE

My Life With Erwin: The Beginning of an Atom-Probe Legacy
John A. Panitz 274

RECONSTRUCTION

Atom Probe Reconstruction With a Locally Varying Emitter Shape
Daniel Beinke and Guido Schmitz 280

Introducing a Crystallography-Mediated Reconstruction (CMR) Approach to Atom Probe Tomography
Alec C. Day, Anna V. Ceguerra and Simon P. Ringer 288

Calibration of Atom Probe Tomography Reconstructions Through Correlation with Electron Micrographs
Isabelle Mouton, Shyam Katnagallu, Surendra Kumar Makineni, Oana Cojocaru-Mirédin, Torsten Schwarz, Leigh Thomas Stephenson, Dierk Raabe and Baptiste Gault 301

Assessing the Spatial Accuracy of the Reconstruction in Atom Probe Tomography and a New Calibratable Adaptive Reconstruction
Anna V. Ceguerra, Alec C. Day and Simon P. Ringer 309

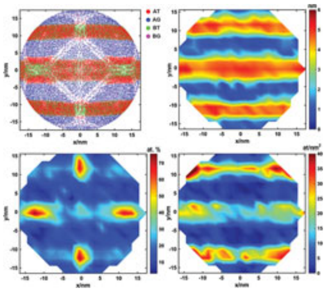
DATA ANALYSIS

Building a Library of Simulated Atom Probe Data for Different Crystal Structures and Tip Orientations Using TAPSim
Markus Kühbach, Andrew Breen, Michael Herbig and Baptiste Gault 320

DF-Fit: A Robust Algorithm for Detection of Crystallographic Information in Atom Probe Tomography Data
Daniel Haley, Paul A. J. Bagot and Michael P. Moody 331

The Application of the OPTICS Algorithm to Cluster Analysis in Atom Probe Tomography Data
Jing Wang, Daniel K. Schreiber, Nathan Bailey, Peter Hosemann and Mychailo B. Toloczko 338

A Precise Method for Analysis of Elemental Distribution Inside Solute Clusters
Takumi Kitayama, Masaya Kozuka, Yasuhiro Aruga and Chikara Ichihara 349



On the Cover: Atom probe tomography top views of a grain boundary obtained from a simulated dataset. Clockwise from top left, atom map, thickness map, Gibbsian interfacial excess map and concentration map. For further detail see paper by Peng et al, page 389-400.

https://doi.org/10.1017/S1431927619000576 Published online by Cambridge University Press

Atom Probe Tomography Interlaboratory Study on Clustering Analysis in Experimental Data Using the Maximum Separation Distance Approach
Yan Dong, Auriane Etienne, Alex Frolov, Svetlana Fedotova, Katsuhiko Fujii, Koji Fukuya, Constantinos Hatzoglou, Evgenia Kuleshova, Kristina Lindgren, Andrew London, Anabelle Lopez, Sergio Lozano-Perez, Yuichi Miyahara, Yasuyoshi Nagai, Kenji Nishida, Bertrand Radiguet, Daniel K. Schreiber, Naoki Soneda, Mattias Thuvander, Takeshi Toyama, Jing Wang, Faiza Sefta, Peter Chou and Emmanuelle A. Marquis 356

Enhancing Element Identification by Expectation–Maximization Method in Atom Probe Tomography
Francois Vurpillot, Constantinos Hatzoglou, Bertrand Radiguet, Gerald Da Costa, Fabien Delaroche and Frederic Danoix 367

Quantifying Uncertainty from Mass-Peak Overlaps in Atom Probe Microscopy
Andrew J. London 378

An Automated Computational Approach for Complete In-Plane Compositional Interface Analysis by Atom Probe Tomography
Zirong Peng, Yifeng Lu, Constantinos Hatzoglou, Alisson Kwiatkowski da Silva, Francois Vurpillot, Dirk Ponge, Dierk Raabe and Baptiste Gault 389

The Influence of Isoconcentration Surface Selection in Quantitative Outputs from Proximity Histograms
Dallin J. Barton, B. Chad Hornbuckle, Kristopher A. Darling and Gregory B. Thompson 401

INSTRUMENTATION AND EXPERIMENTAL METHODOLOGY

A Gas-Phase Reaction Cell for Modern Atom Probe Systems
Daniel Haley, Ingrid McCarroll, Paul A. J. Bagot, Julie M. Cairney and Michael P. Moody 410

Spatial and Compositional Biases Introduced by Position Sensitive Detection Systems in APT: A Simulation Approach
C. Bacchi, G. Da Costa and F. Vurpillot 418

A Study of Parameters Affecting Atom Probe Tomography Specimen Survivability
Ty J. Prosa, Savanna Strennen, David Olson, Dan Lawrence and David J. Larson 425

Fabrication of Atom Probe Tomography Specimens from Nanoparticles Using a Fusible Bi–In–Sn Alloy as an Embedding Medium
Se-Ho Kim, Ji Yeong Lee, Jae-Pyoung Ahn and Pyuck-Pa Choi 438

MATERIALS SCIENCE: METALS

Atom Probe Compositional Analysis of Interphase Precipitated Nano-Sized Alloy Carbide in Multiple Microalloyed Low-Carbon Steels
Yongjie Zhang, Goro Miyamoto and Tadashi Furuhara 447

Improving Compositional Accuracy in APT Analysis of Carbides Using a Decreased Detection Efficiency
Mattias Thuvander, Deodatta Shinde, Arbab Rehan, Sebastian Ejnermark and Krystyna Stiller 454

Analyzing Boron in 9–12% Chromium Steels Using Atom Probe Tomography
Irina Fedorova, Flemming Bjerg Grumsen, John Hald, Hans-Olof Andrén and Fang Liu 462

Atom Probe Microscopy of Strengthening Effects in Alloy 718
Felix Theska, Simon Peter Ringer and Sophie Primig 470

Quantification Challenges for Atom Probe Tomography of Hydrogen and Deuterium in Zircaloy-4
Isabelle Mouton, Andrew J. Breen, Siyang Wang, Yanhong Chang, Agnieszka Szczepaniak, Paraskevas Kontis, Leigh T. Stephenson, Dierk Raabe, M. Herbig, T. Ben Britton and Baptiste Gault 481

Elemental Distribution in CrNbTaTiW-C High Entropy Alloy Thin Films
Deodatta Shinde, Stefan Fritze, Mattias Thuvander, Paulius Malinovskis, Lars Riekehr, Ulf Jansson and Krystyna Stiller 489

https://doi.org/10.1017/S1431927619000576 Published online by Cambridge University Press

Charge-State Field Evaporation Behavior in Cu(V) Nanocrystalline Alloys
Xuyang Zhou and Gregory B. Thompson 501

MATERIALS SCIENCE: NON-METALS

Quantitative Aspects of PLAD Sidewall Doping Characterization by SIMS and APT
Dimitry Kouzminov, James Cournoyer, Somchintana Norasetthekul, Harish Muthuraman and Qi Gao 511

Coupling Secondary Ion Mass Spectrometry and Atom Probe Tomography for Atomic Diffusion and Segregation Measurements
Alain Portavoce, Khalid Hoummada and Lee Chow 517

Quantitative Determination of How Growth Conditions Affect the 3D Composition of InGaAs Nanowires
Jiangtao Qu, Hansheng Chen, Mansoor Khan, Fan Yun, Xiangyuan Cui, Simon P. Ringer, Julie M. Cairney and Rongkun Zheng 524

Microstructural Characterization of Sulfurization Effects in Cu(In,Ga) Se_2 Thin Film Solar Cells
Hisham Aboulfadl, Jan Keller, Jes Larsen, Mattias Thuvander, Lars Riekehr, Marika Edoff and Charlotte Platzer-Björkman 532

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Rick Verberne, David W. Saxey, Steven M. Reddy, William D. A. Rickard, Denis Fougerouse and Chris Clark 539

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Toshiharu Ohnuma 547

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